



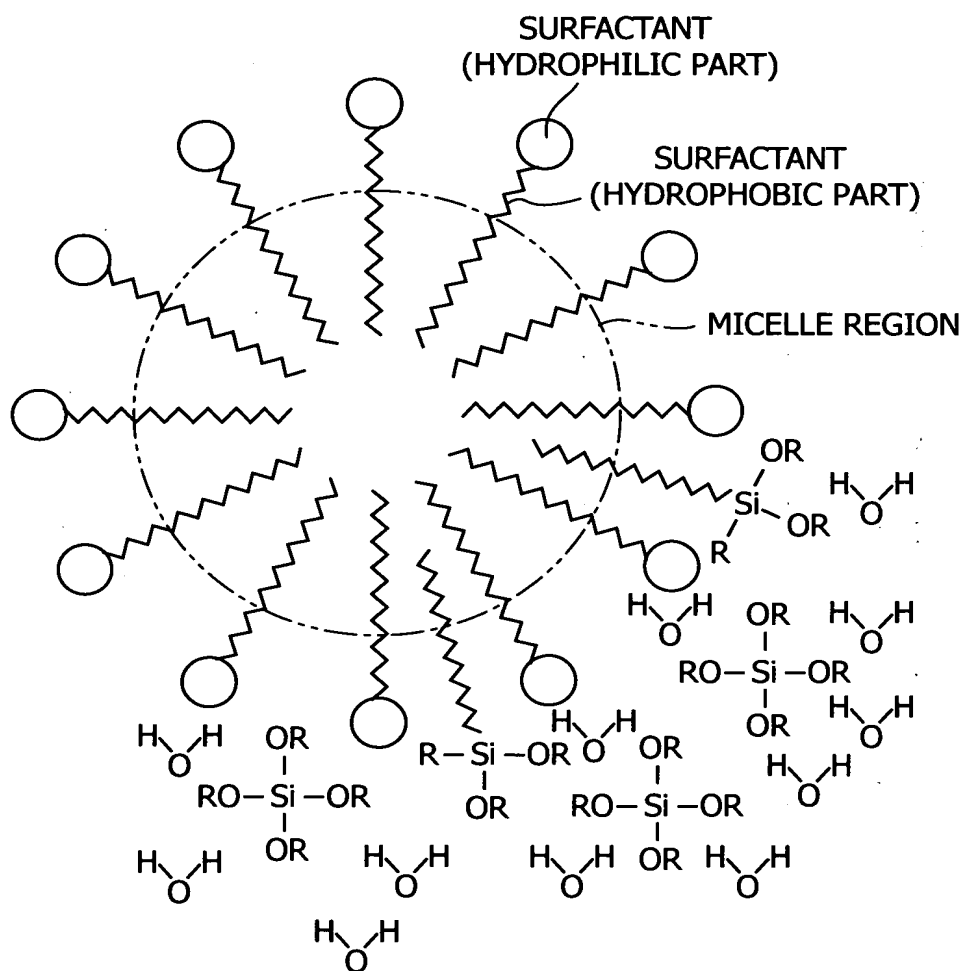
Title: Composition for Forming Porous Film, Porous Film and Method for Forming the Same, Interlevel Insulator Film, and Semiconductor Device

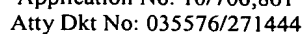
Inventor(s): Hamada et al.

Application No: 10/706,861

Atty Dkt No: 035576/271444

FIG.1



[illegible]